



Rodel® Finishing Pads

DESCRIPTION

All Rodel poromeric pads are designed to produce a featureless, exacting surface finish. Developed through laboratory and customer testing, each product has unique polishing characteristics based on combinations of the elements of pore structure, urethane density and substrate composition. These unique characteristics allow Rodel finishing pads to work effectively under a wide variety of polishing conditions and permit maximum compatibility with individual processes.

SPM3100

The newest poromeric technology developed by Rodel for silicon final polishing, the SPM3100 features a proprietary pore structure grown directly on a Mylar substrate. The simplicity of this design combined with the unique pore structure reduces variations in pad physical properties, ultimately leading to more consistent performance throughout the life of the pad and a much lower nanoscratch level. The SPM3100 is recommended as a final pad for all polishing operations where surface finish is most critical as defined by haze, microscratches, roughness and light point defects.



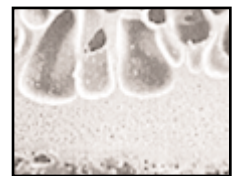
DPC6350

DPC6350 is a grown-in-place poromeric on a urethane impregnated substrate that incorporates a vertically-oriented pore structure similar to the Politex® Supreme material, yet with a moderately less compressible and thinner substrate. This combination provides optimum removal rate and surface finish while maintaining dub-off when polishing nickel plated memory disks and glass substrates. DPC6350 is an improved version of the industry standard, Politex® DG, providing more consistent pore structure within lots of material and lot-to-lot. The smoother finish makes this an excellent pad for final polish due to lower microwaviness, roughness, and faster break-in.



POLITEX® SUPREME

Rodel's signature technology, Politex® Supreme, was originally developed for final wafer polishing. It is manufactured from Rodel's proprietary polyurethane and incorporates a unique, vertically oriented pore structure with a compressible substrate. The substrate is designed to instantaneously recover from polishing compression, creating a pumping action that enhances slurry flow within the pad to produce optimum surface finish quality. This attribute reduces pad loading and increases pad life. This pad is available with a longer nap height which is well suited for final polishing of silicon, oxide, glass or metals.





TYPICAL PAD PROPERTIES

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Product	Thickness	Pore Height	Microporous	Pore Count
Politex Supreme High Nap.	0.060"	0.020"	0.006"	N/A
Politex Supreme Regular Nap	0.056"	0.015"	0.006"	N/A
SPM 3100	0.028"	0.0205"	N/A	N/A
DPC6350	0.041"	0.020"	0.008"	400

These values represent typical measurements. Actual values may vary in a range defined by product specifications.

All Rodel final polishing pads can be die-cut to specified sizes and shapes to fit your polishing platen.

Most pad surfaces can be embossed, perforated or grooved to modify slurry flow and influence pad aggressiveness. The embossing pattern is a 0.100" square grid pattern, .011"-.024" deep in the pad surface. Perforations extend through the entire pad thickness and are in a pattern of approximately 22 holes per square inch. Various groove patterns are available.

All pads are available with or without pressure sensitive adhesive.

PLATEN APPLICATION

Apply only to a clean, dry surface at room temperature. If an appropriate solvent, such as isopropyl alcohol, is used to clean the platen after a pad removal allow the platen to dry completely and return to room temperature before applying the pad. Solvents remaining on the platen, or an unusually cold platen, will lower PSA adhesion.

When applying the pad to the platen, peel the release liner from one edge of the pad. Fold liner back approximately two inches. Align the pad with the edge of the platen and adhere. In one continuous movement, slowly peel the remaining release liner off the pad while pressing the pad down on the platen. The application should be smooth and uniform with even pressure from the pad mounting tool (such as a flat disk or hand roller).

Rodel also provides technical support for specific customer needs and requirements. Please contact your local account manager for further details.

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